

Helium and Nitrogen Purifiers

- Point-of-use purification to low ppm levels
- CE-compliant
- Simple maintenance
- Self-regulated 24 VDC power



Description and Operating Principle

Carrier gas purity is essential in any application requiring extreme sensitivity. Impurities limit detector sensitivity and can even destroy capillary columns. The Valco HP2 (helium purifier) provides "point-of-use" purification of helium or other noble gases, such as Ar, Ne, Kr, and Xe, to sub-ppm levels of reactive gaseous impurities. The NP2 (nitrogen purifier) is similar, purifying nitrogen to sub-ppm levels of gaseous impurities.

The purification substrate in Valco gas purifiers is a nonevaporable gettering alloy. This stable alloy is contained in a welded assembly, so the purifiers can be used safely in industrial applications with minimal precautions. The getter is activated by heating, which eliminates the oxide film on the particle surface and allows helium to diffuse into the bulk of the getter particles. This leaves the surface free from the passivating oxide layers and available for sorption. Activation must be performed under a vacuum or inert gas (He, Ar, Kr, or Xe) atmosphere. The helium and nitrogen purifiers feature a self-regulating design which eliminates the possibility of thermal runaway and maintains the getter material at the optimum temperature.

Specifications

Helium Purifier (HP2) Nitrogen Purifier (NP2) Gases purified He, Ne, Ar, Kr, Xe, Rn He, Ne, Ar, Kr, Xe, Rn, N₂ Max. operating pressure 1000 psig 1000 psig 400°C 400°C Max. operating temperature Max. flow rate 1 liter/min 1 liter/min Outlet impurities less than 10 ppb Impurities removed Outlet impurities less than 10 ppb H₂O, H₂, O₂, N₂, NO, NH₃, CO, H₂O, H₂, O₂, NO, NH₃, CO, and and CO₂, based on 100 ppm total CO₂, based on 100 ppm total inlet inlet impurities. Other impurities impurities. Other impurities removed removed include CF₄, CCl₄, SiH₄, include CF₄, CCl₄, SiH₄, and hydrocarbons other than CH₄ and hydrocarbons such as CH₄ Impurities not removed He, Ne, Ar, Kr, Xe, Rn, CH₄, and N₂ He, Ne, Ar, Kr, Xe, and Rn



Miniature Gas Purifiers

Virtually all commercial gas chromatographs contain certain components which, while adequate for flame ionization and thermal conductivity detectors, are unsuitable for low ppb universal analyses. For



example, unheated molecular sieve traps are certain to contaminate the carrier gas with CO_2 and H_2O .

The Valco Miniature Helium Purifier (HPM) and Miniature Nitrogen Purifier (NPM) are designed to address this situation, providing "point-of-use" carrier gas purification to sub-ppm levels of gaseous impurities. When installed in a gas chromatograph's flow path immediately upstream of the injector, the HPM/NPM will remove any contaminants introduced by flow controllers, elastomeric tube seals, pressure regulators, crude traps, or other system components that are not completely clean and leak-tight.

Specifications

	Helium Purifier (HPM)	Nitrogen Purifier (NPM)
Gases purified	He, Ne, Ar, Kr, Xe, Rn	He, Ne, Ar, Kr, Xe, Rn, N ₂
Max. operating pressure	200 psig	200 psig
Max. operating temperature	400°C	400°C
Max. flow rate	30 cc/min	30 cc/min
Impurities removed	Outlet impurities less than 10 ppb H_2O , H_2 , O_2 , N_2 , NO , NH_3 , CO , and CO_2 , based on 100 ppm total inlet impurities. Other impurities removed include CF_4 , CCI_4 , SiH_4 , and hydrocarbons such as CH_4	Outlet impurities less than 10 ppb H ₂ O, H ₂ , O ₂ , NO, NH ₃ , CO, and CO ₂ , based on 100 ppm total inlet impurities. Other impurities removed include CF ₄ , CCl ₄ , SiH ₄ , and hydrocarbons other than CH ₄
Impurities not removed	He, Ne, Ar, Kr, Xe, and Rn	He, Ne, Ar, Kr, Xe, Rn, $\mathrm{CH_4}$, and $\mathrm{N_2}$

Ordering Information

Description Product numbers

Standard helium and nitrogen purifiers

 Helium
 Nitrogen

 110 VAC
 HP2
 NP2

 220 VAC
 HP2-220
 NP2-220

 Replacement getter assembly
 I-23572
 I-23572NP2

Miniature helium and nitrogen purifiers

 Helium
 Nitrogen

 110 VAC
 HPM
 NPM

 220 VAC
 HPM-220
 NPM-220



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